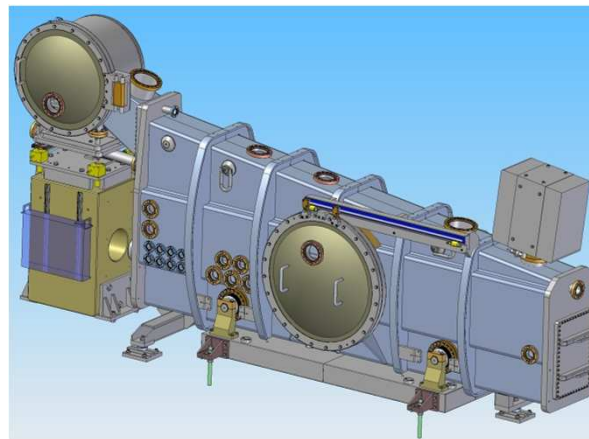
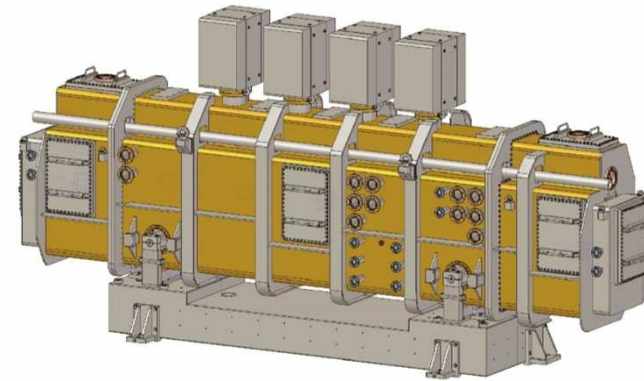
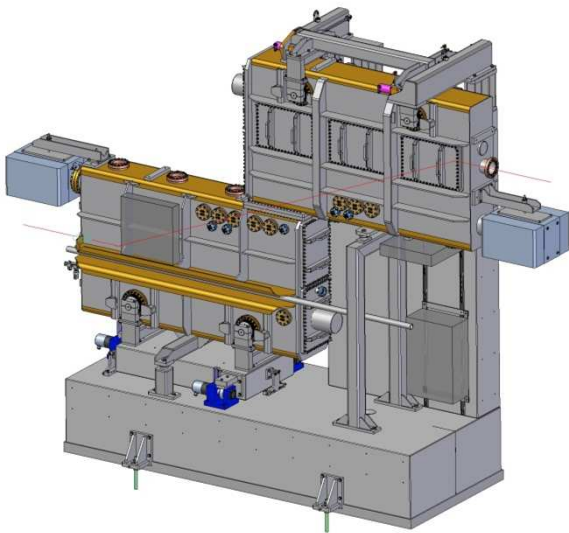


Optical Components at Petra III

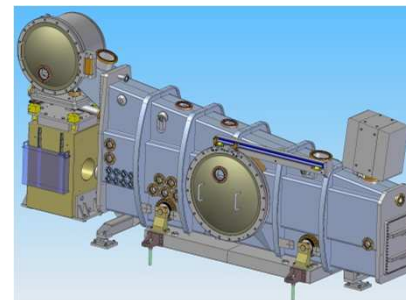
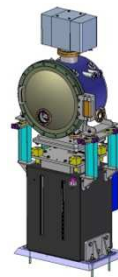
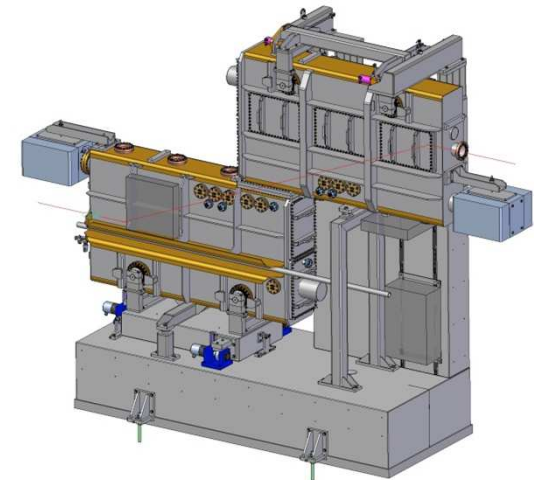
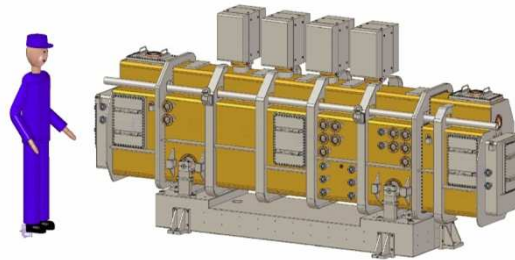
Highlighting the challenges and solutions



Jan Horbach
ESRF Seminar
17th October 2011

Outline

- Overview Petra III
- Mono-P06
- LOM 500
- LOM 1250
- Diamond/Silicon Laue monochromator P02.1
- Generic high heat load monochromator
- Mirror optics
- Generic Frontend
- Outlook



Overview Petra III



- 3rd Generation Synchrotron Radiation Source
- Accelerator perimeter: 2304 m
- Particle energy: 6 GeV
- Current in top up mode : 100 mA (200 mA)
- Emittance: 1 nm rad
- 14 Beamlines (5° angular distance)
- 1 x 10 m undulator
- 1 x 5 m undulator
- 1 x 5 m apple undulator
- 1 x 4m in vacuum undulator
- 5 x (2 x 2 m) canted undulators (5 mrad ~ 0.29° angular distance)

Petra Extension: 10 new beamlines in 2 new experimental halls



Overview Petra III

- P01: Inelastic and nuclear resonant scattering
- P02: Hard X-Ray diffraction
- P03: Micro and nano Saxs/Waxs
- P04: Variable polarization soft X-Ray
- P05: Micro- and nano-tomography (HZG)
- P06: Hard X-Ray micro probe and imaging
- P07: High energy materials science (HZG)
- P08: High resolution diffraction
- P09: Resonant scattering/diffraction
- P10: Coherence applications
- P11: Bio imaging/diffraction (HZI, MPG, Desy)
- P12: Bio small angle scattering (EMBL)
- P13: Macro molecular crystallography I (EMBL)
- P14: Macro molecular crystallography II (EMBL)



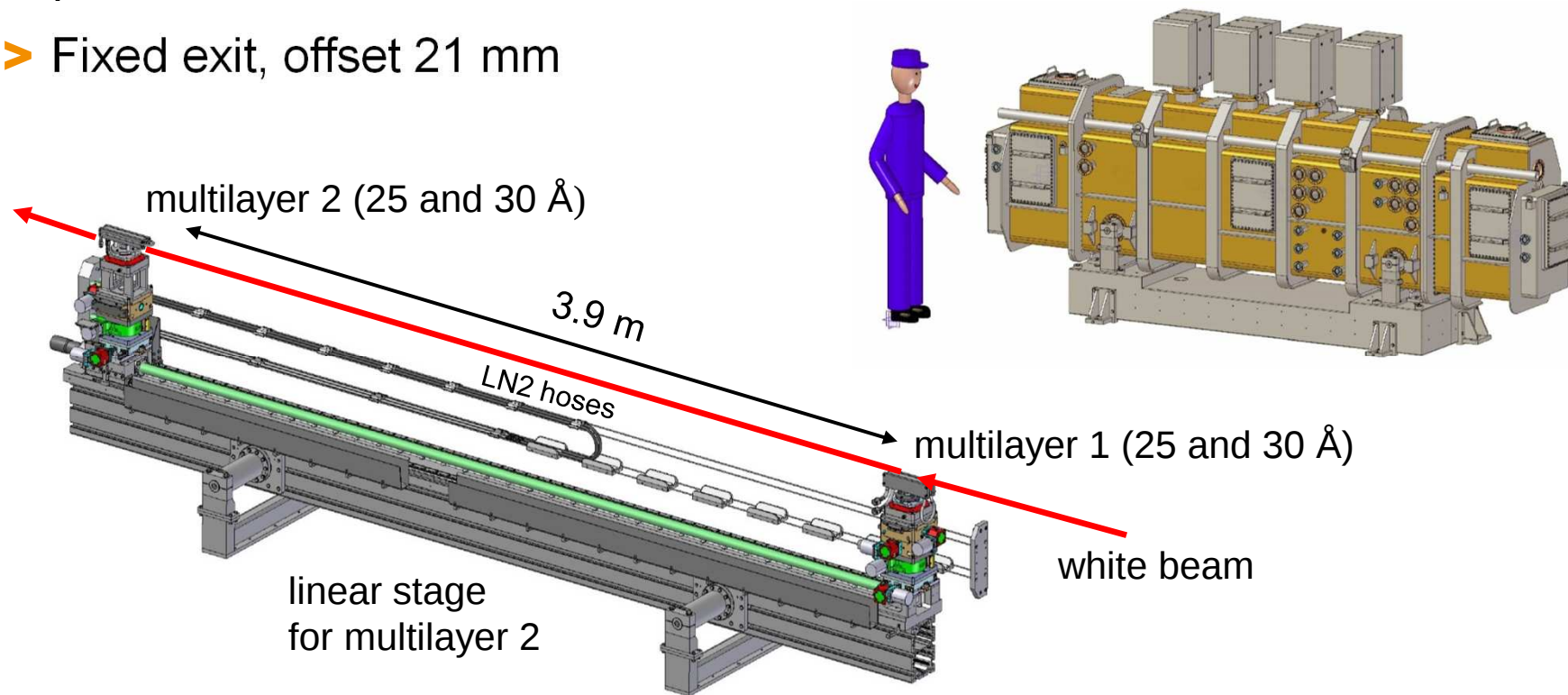
Large Monochromator Systems: Purpose and Specifications

- > Technical solution needed for canted undulator beamlines due to small angular separation
- > White beam (high heat load)
- > Reduction of the energetic bandwidth of a monochromatic beam
- > Energy range of the monochromators adapted to beamline needs
 - P03: 8 – 25 keV
 - P06: 4.4 – 90 keV
 - P08: 5.4 – 29.4 keV



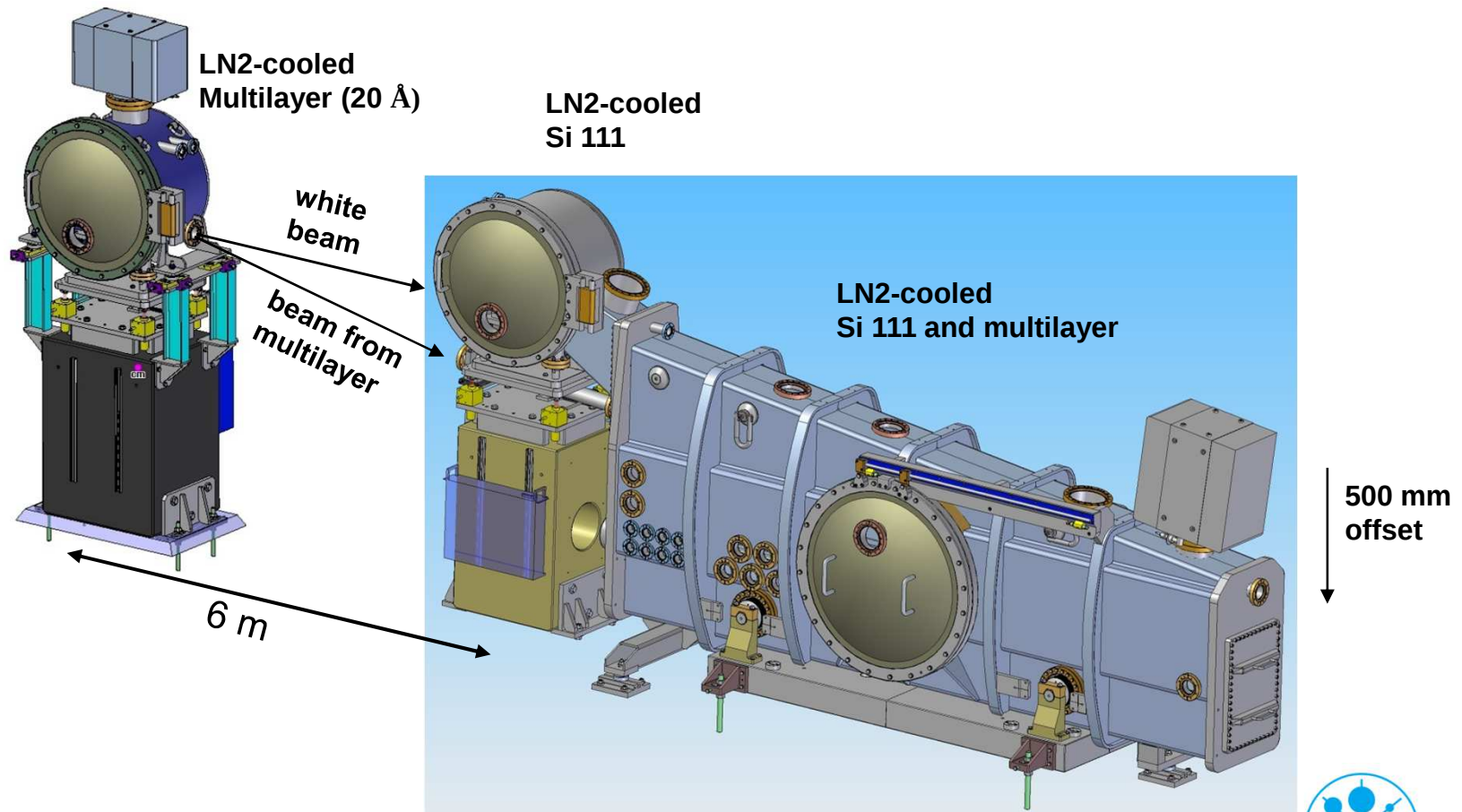
Mono - P06 (Hard X-Ray micro probe and imaging)

- Energy range 4.4 – 90 keV
- Both multilayers (W-Si) are cryocooled
- Deviation along the linear stage smaller than $\pm 240 \mu\text{rad}$ (50 arcsec) in pitch and roll
- Fixed exit, offset 21 mm



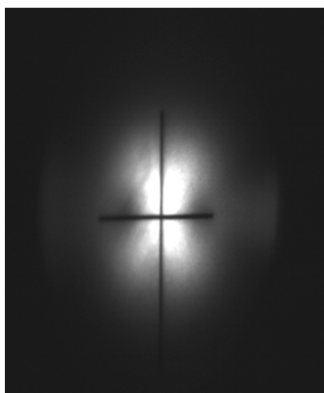
LOM 500 - P03 (Micro and nano Saxs/Waxs)

- > 2 different beam paths for Si 111 crystal set (8 – 25 keV) and multilayers (8.4 – 11.5 keV for 20 Å spacing)
- > All optical components are cryocooled

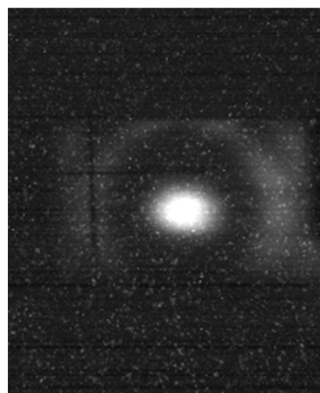


LOM 500 - Commissioning

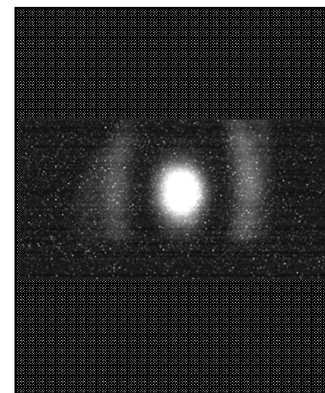
CVD diamond screens with ccd camera:



Screen 1
17 m behind
undulator

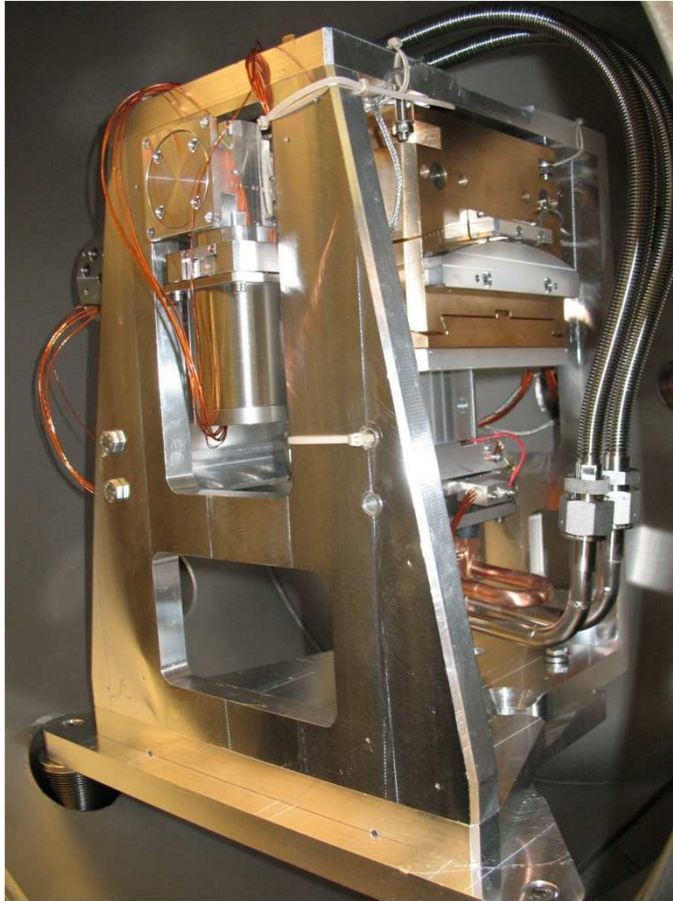


Screen 3
behind first crystal
3rd harmonic 13 keV
54 m behind undulator

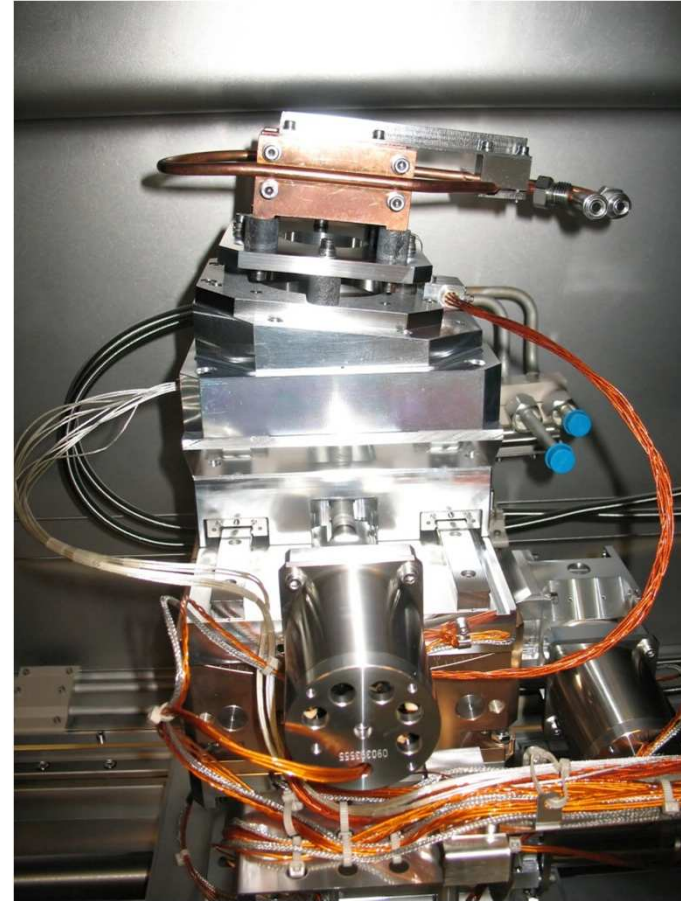


Screen 4
behind second crystal
59 m behind undulator

LOM 500 – crystal set (Si 111)

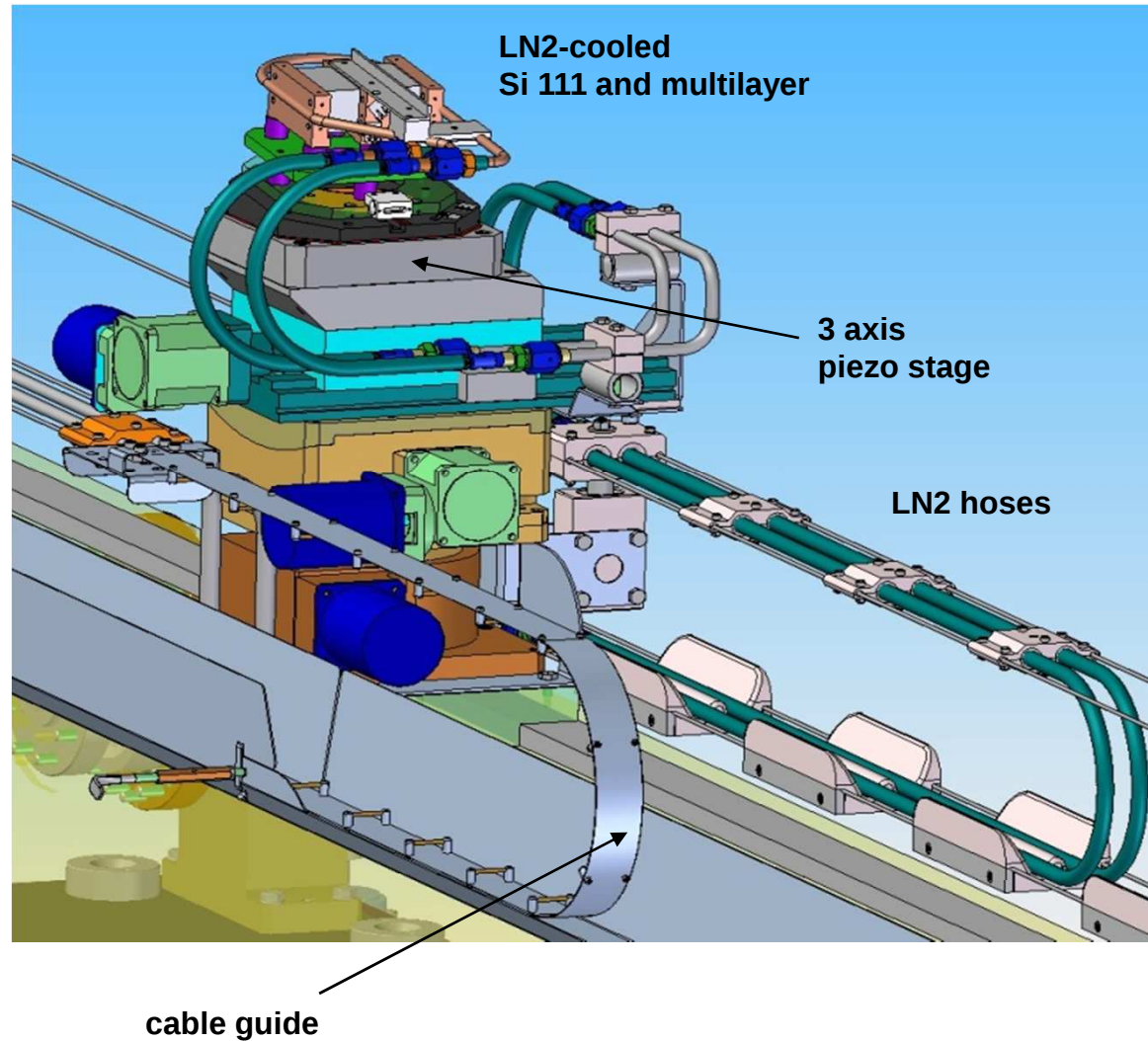


1st crystal

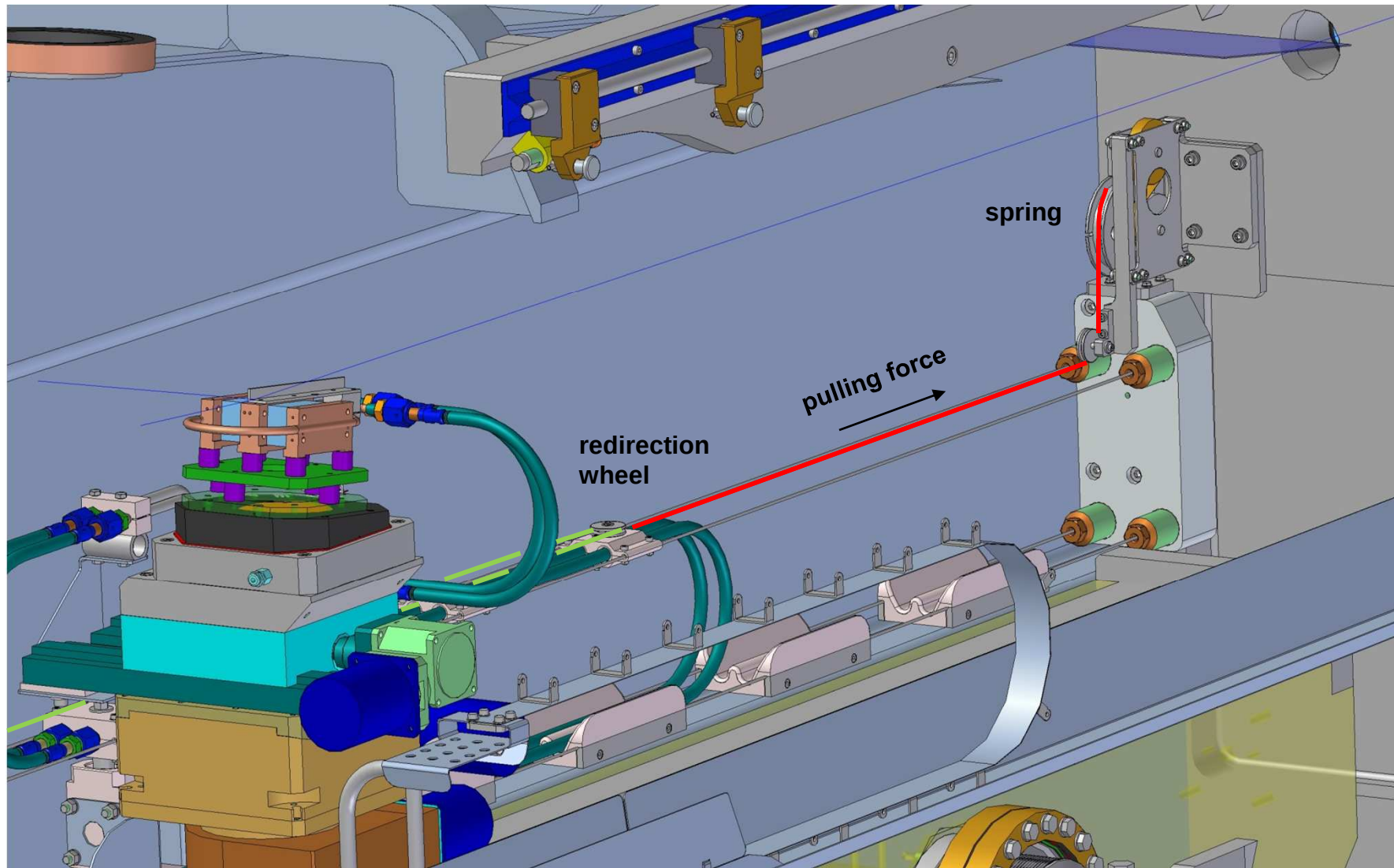


2nd crystal and multilayer
on 2.5 m translation

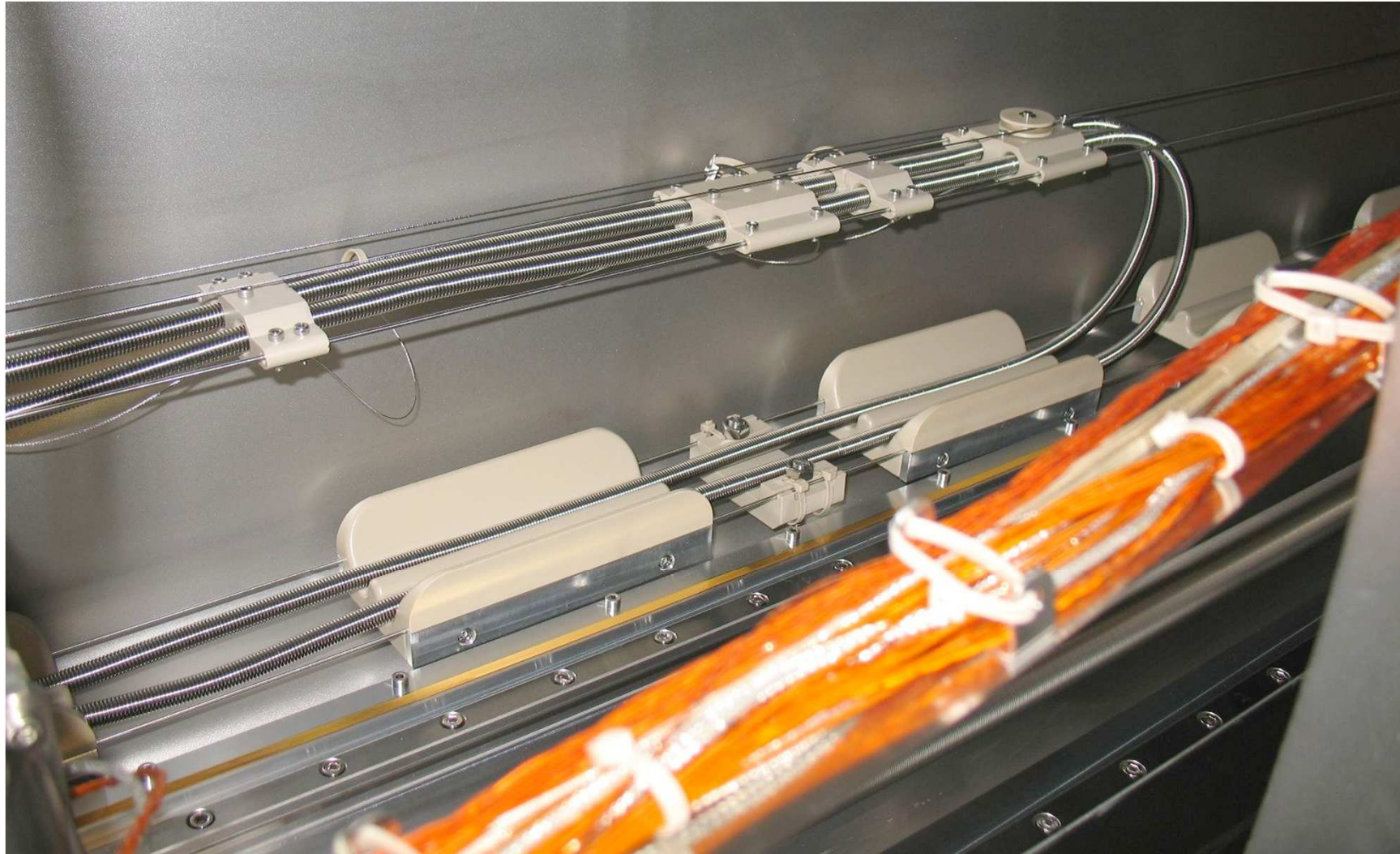
LOM 500 – mechanical details



LOM 500 – mechanical details – 2nd version

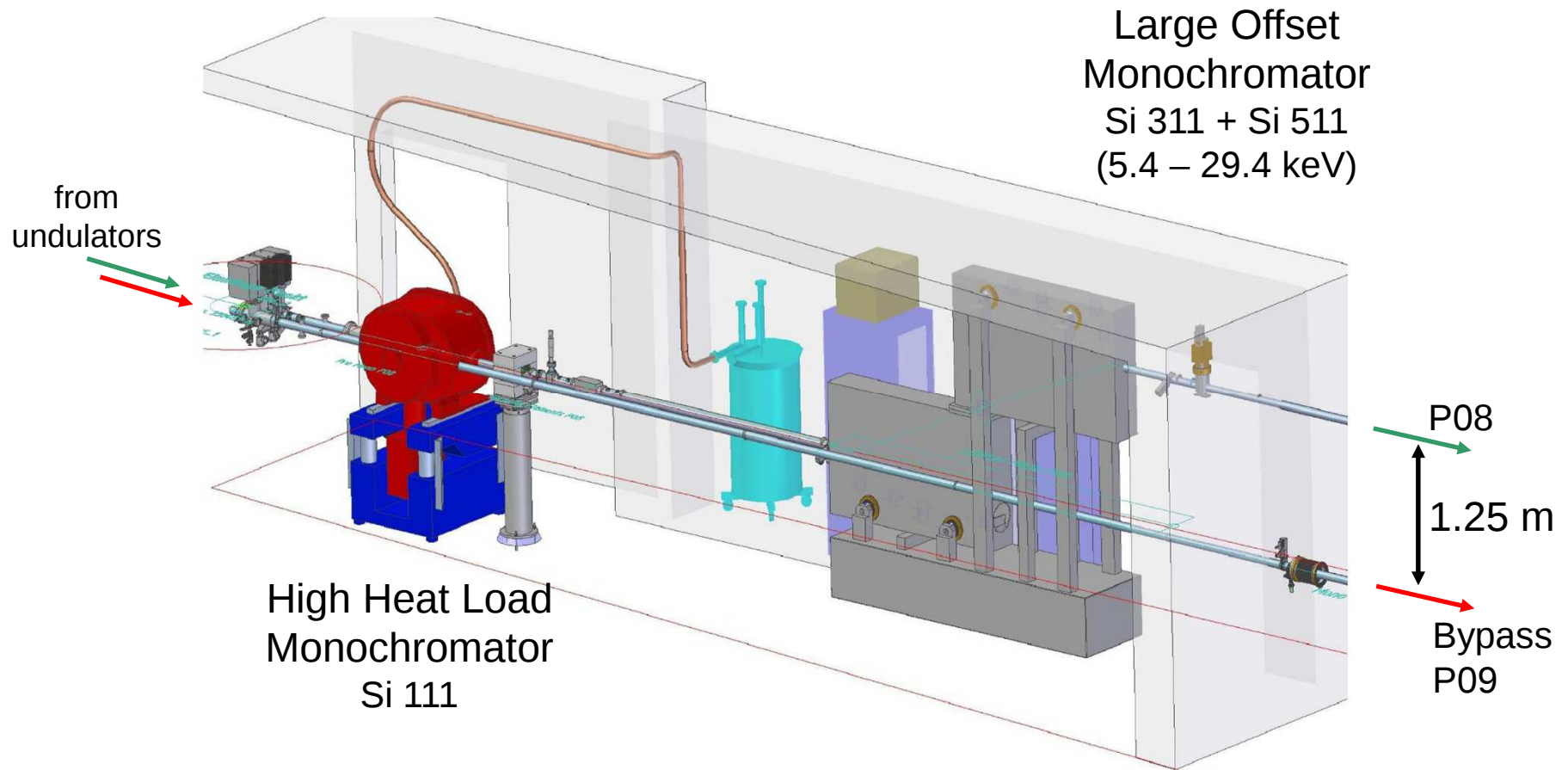


LOM 500 – mechanical details – 3rd version



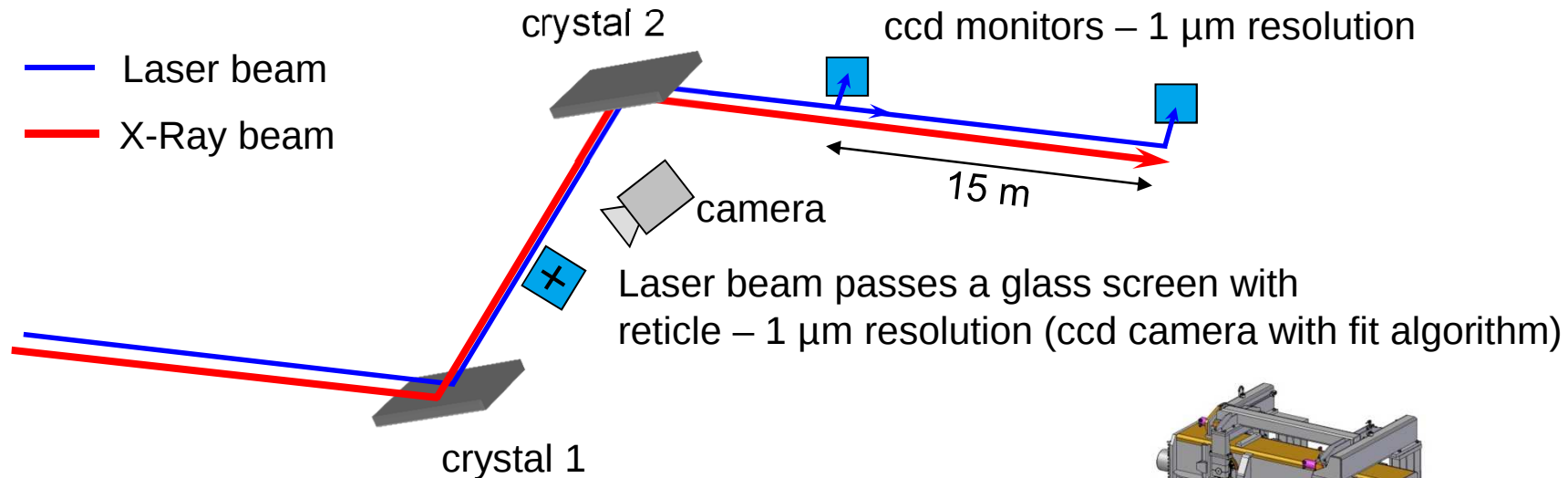
LOM 1250 - P08 (High resolution diffraction)

- accepts monochromatic beam from Generic High Heat Load Monochromator



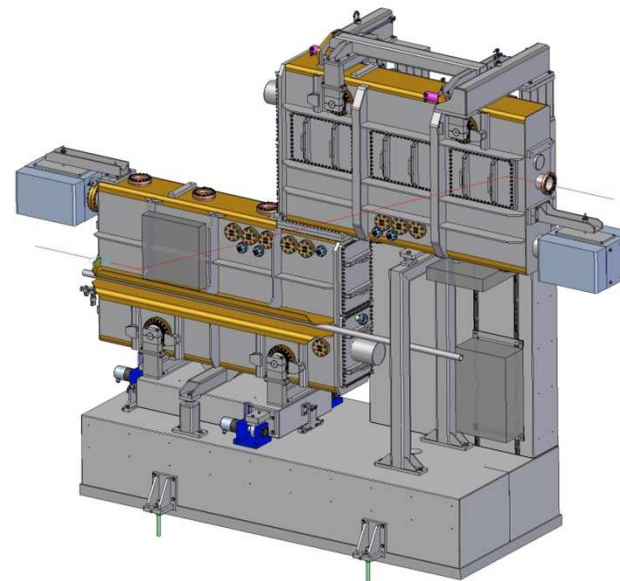
LOM 1250

> Laser stabilisation for compensation of thermal drift



X-Ray beam stability at the experiment (20m behind the LOM 1250): $\pm 4 \mu\text{m}$, equal to $0.2 \mu\text{rad}$

DU4

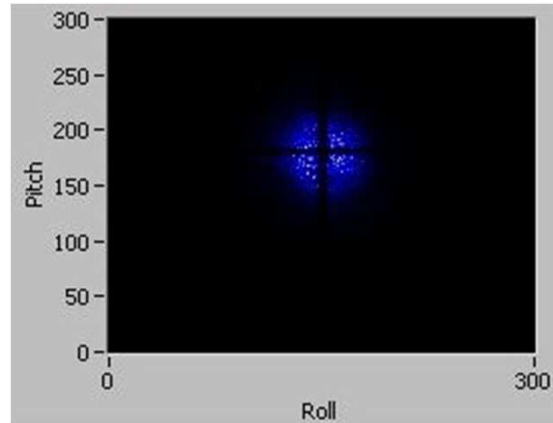


Laser spot at glass screen with reticle

Laser diameter 3 mm

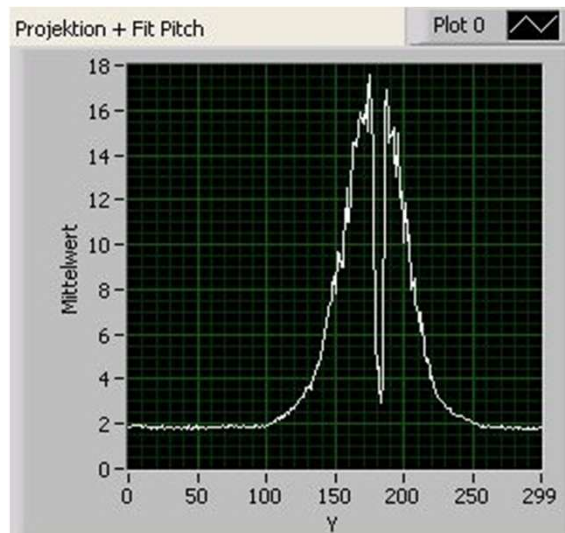
DU5

Projection in pitch
direction



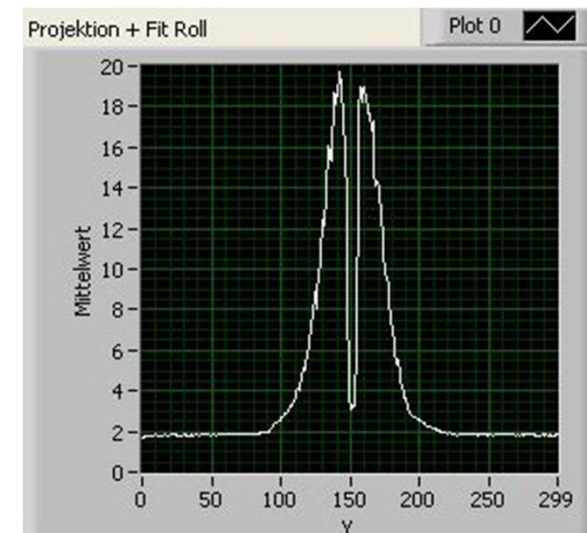
Camera resolution 50
 μm / pixel

Projection in roll
direction

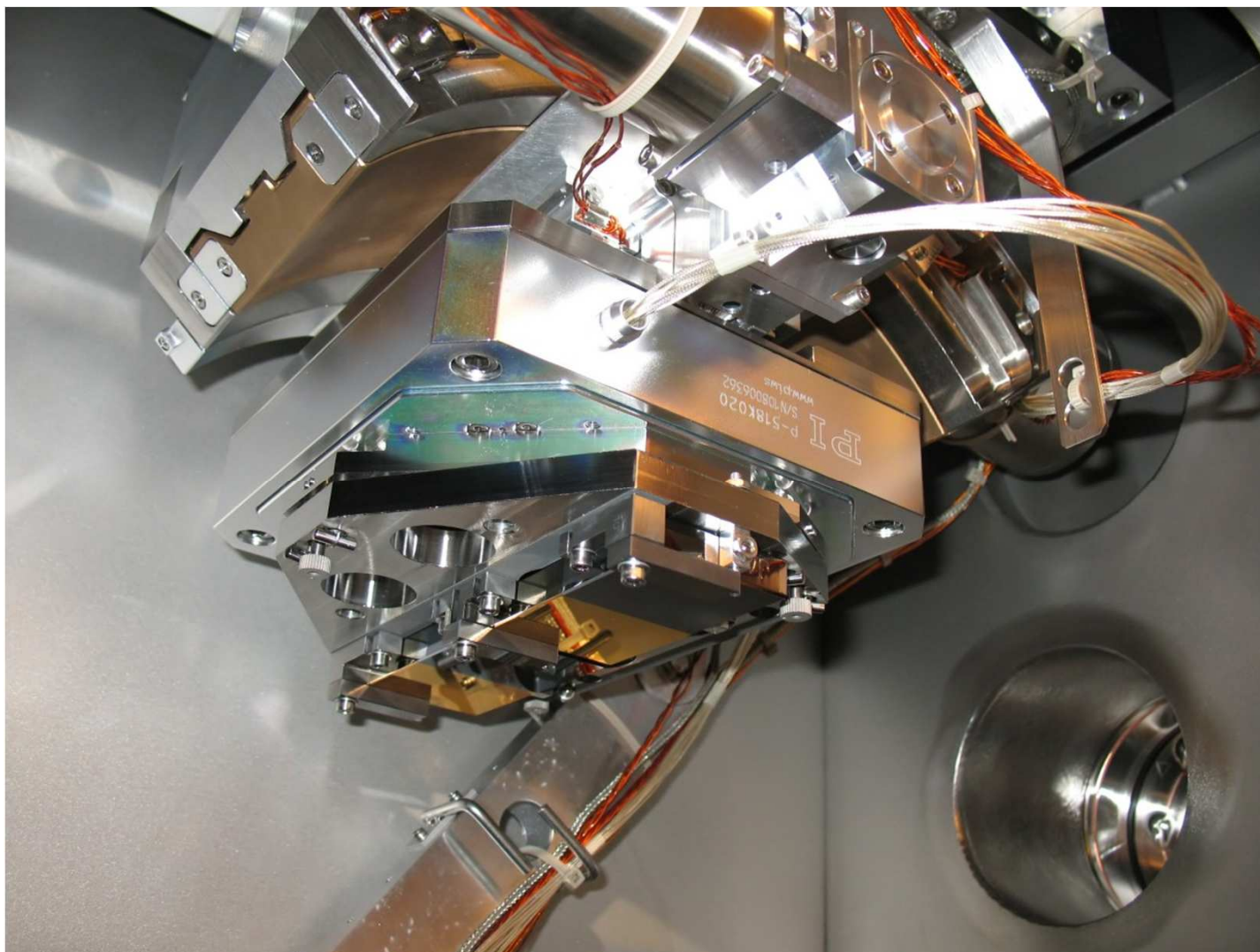


Resolution of
Gaussian fit
approx. $1\mu\text{m}$.

Repetition rate
approx. 5 Hz

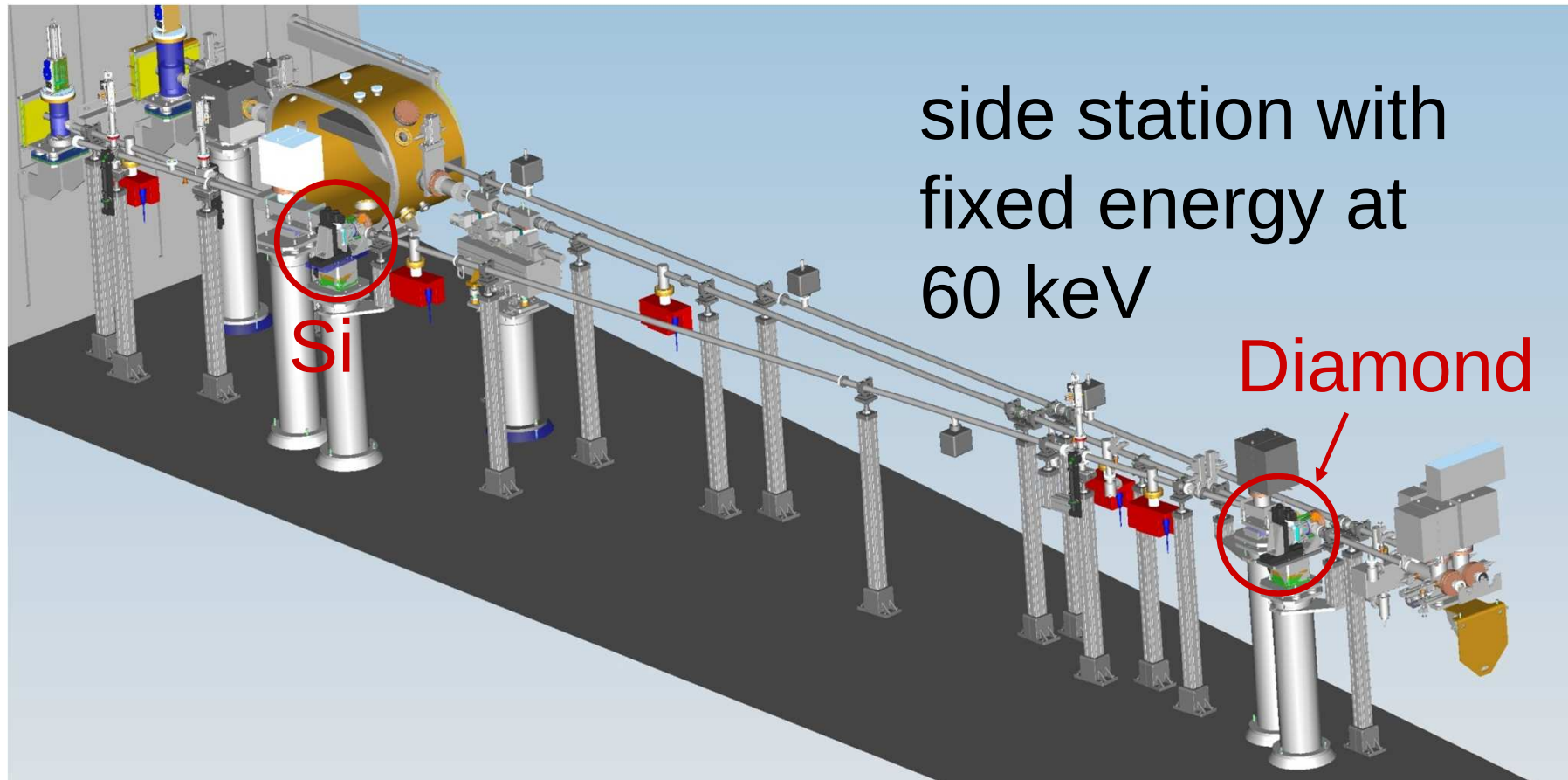


LOM 1250 – 2nd crystal (Si 311 + Si 511)



Miscut between
crystal surface and
crystal planes:
Pitch: 85 μ rad
Roll: 50 μ rad

Diamond / Silicon Laue Monochromator at Beamline P02.1



Diamond / Silicon Laue Monochromator at Beamline P02.1

nickel plated copper
With GaIn foil at
connections

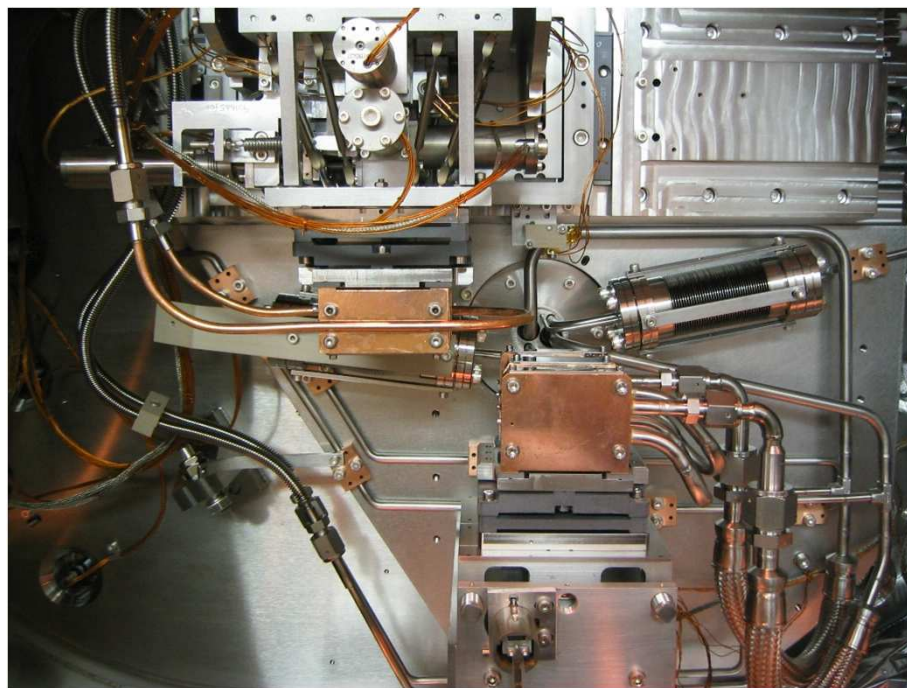


Diamond (100)
In Laue configuration (111)
Thickness 0.4 mm

Generic High Heat Load Monochromator

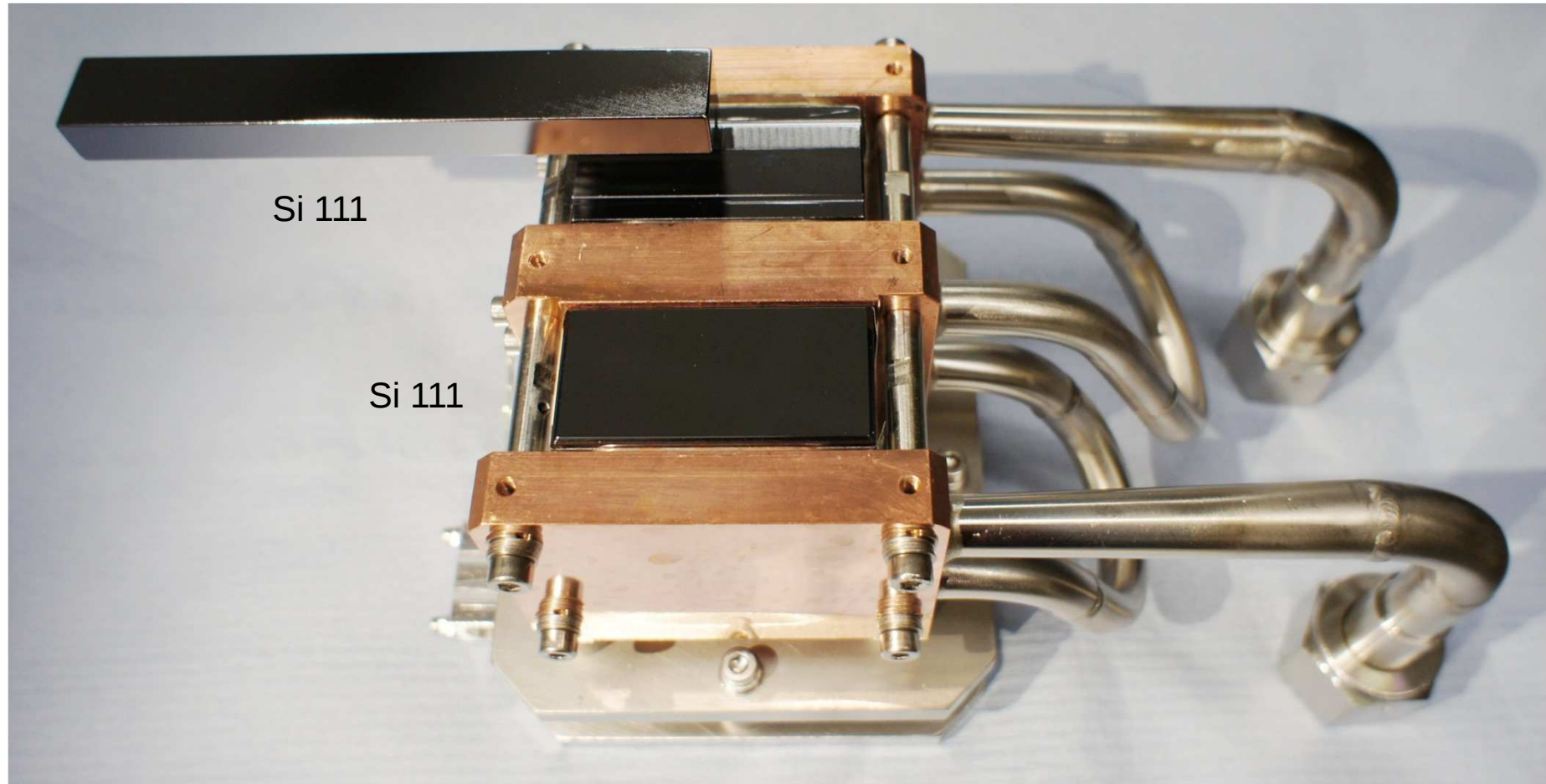


- 50 μ rad resolution of bragg axis
- 18 nrad resolution of bragg piezo
- offset 21 mm upwards



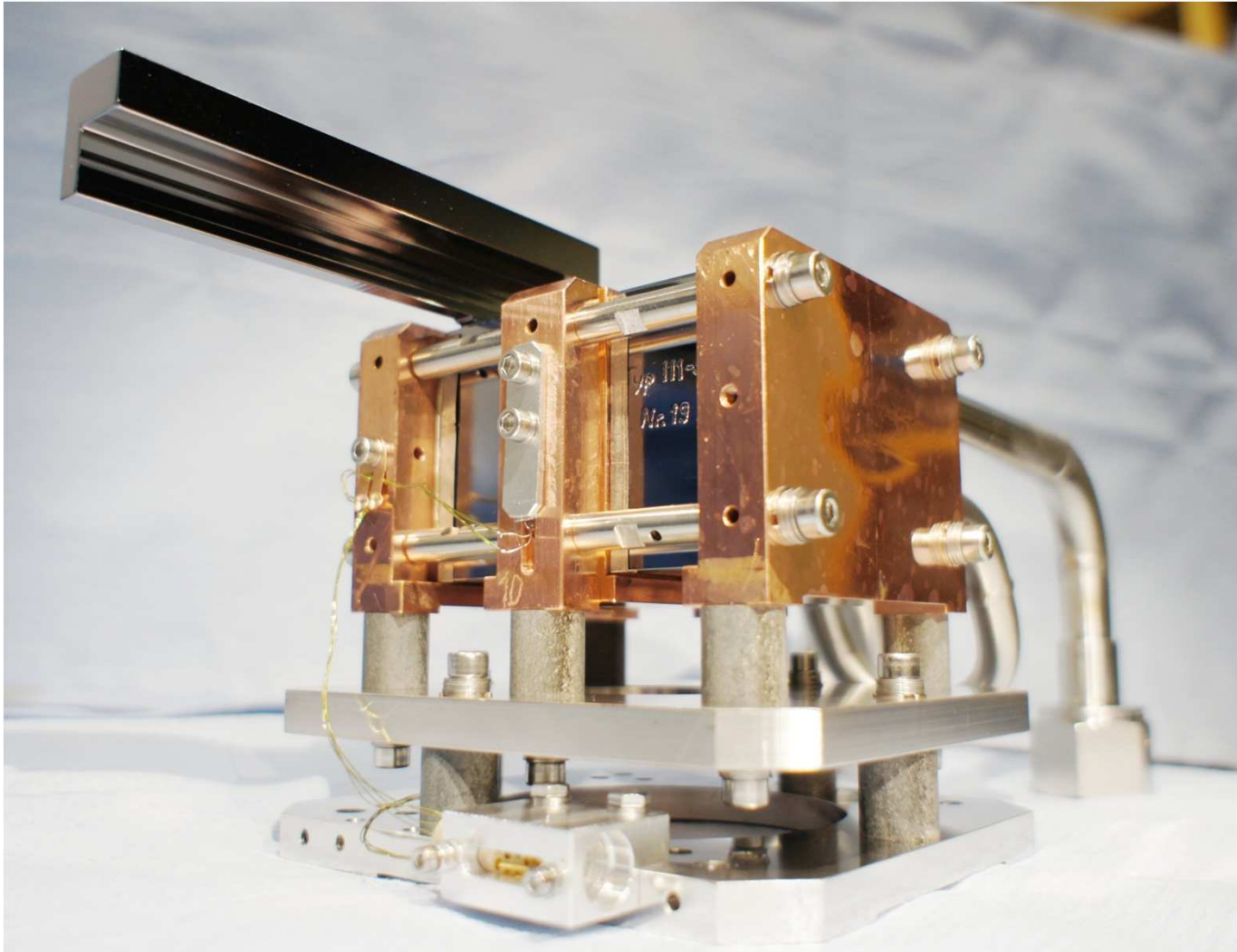
High Heat Load Channel Cut Monochromator P10 (Coherence applications)

first crystal



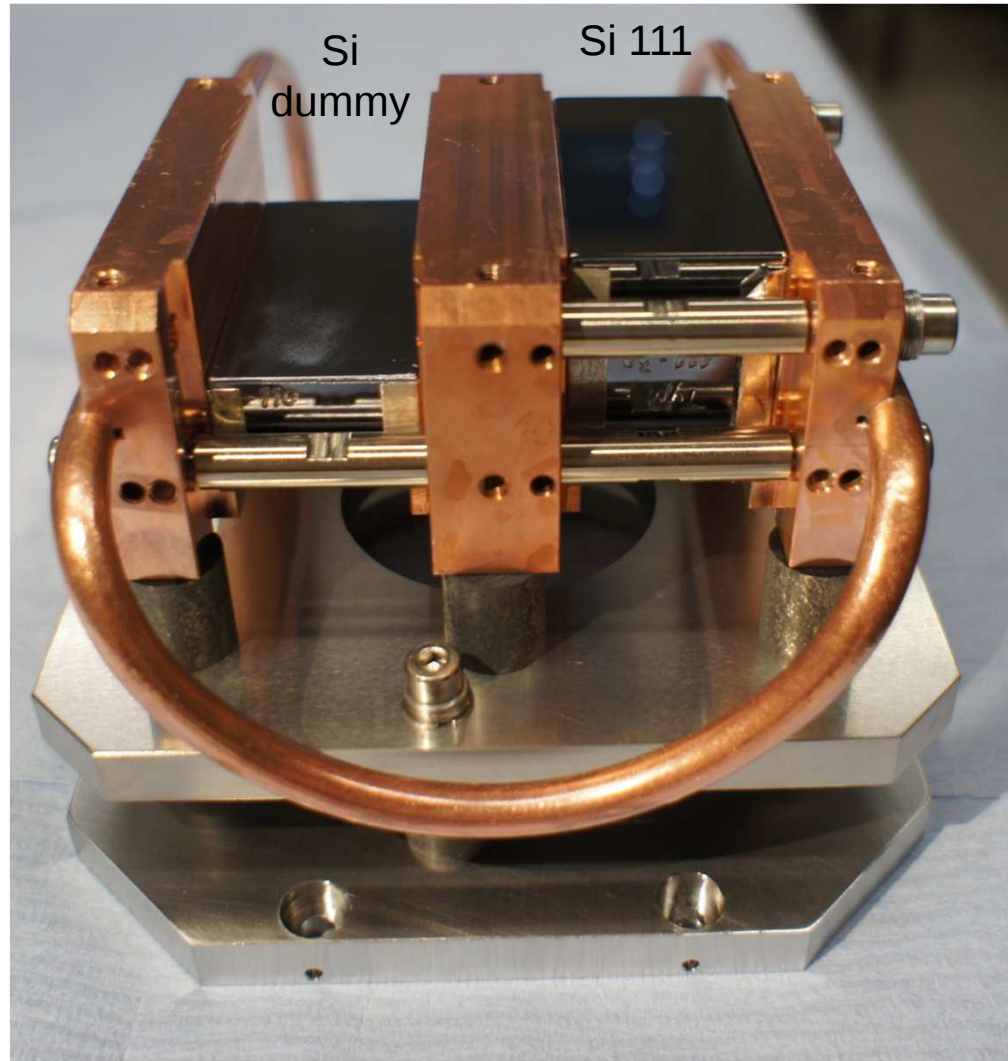
High Heat Load Channel Cut Monochromator P10

first crystal



High Heat Load Channel Cut Monochromator P10

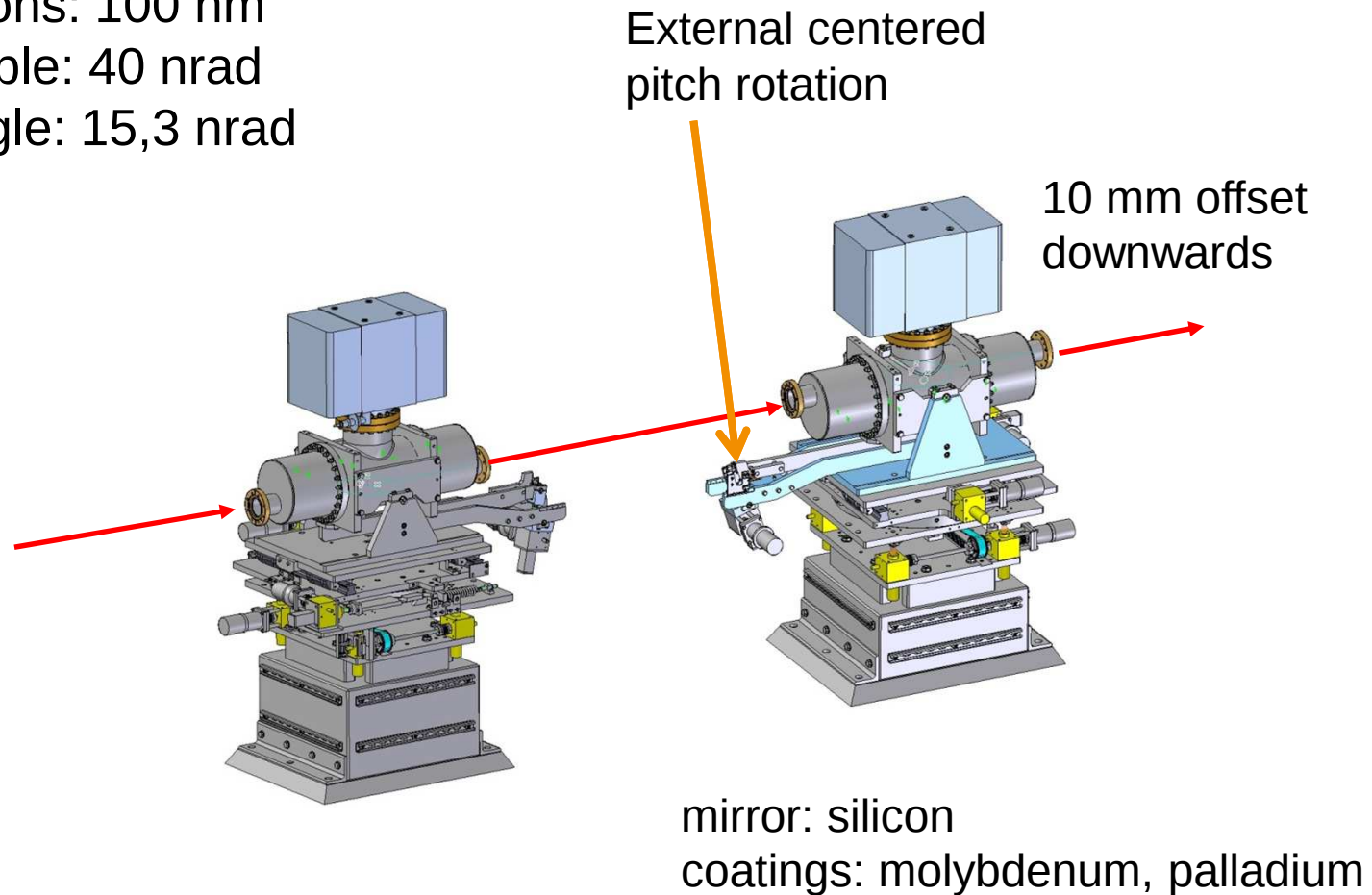
second
crystal



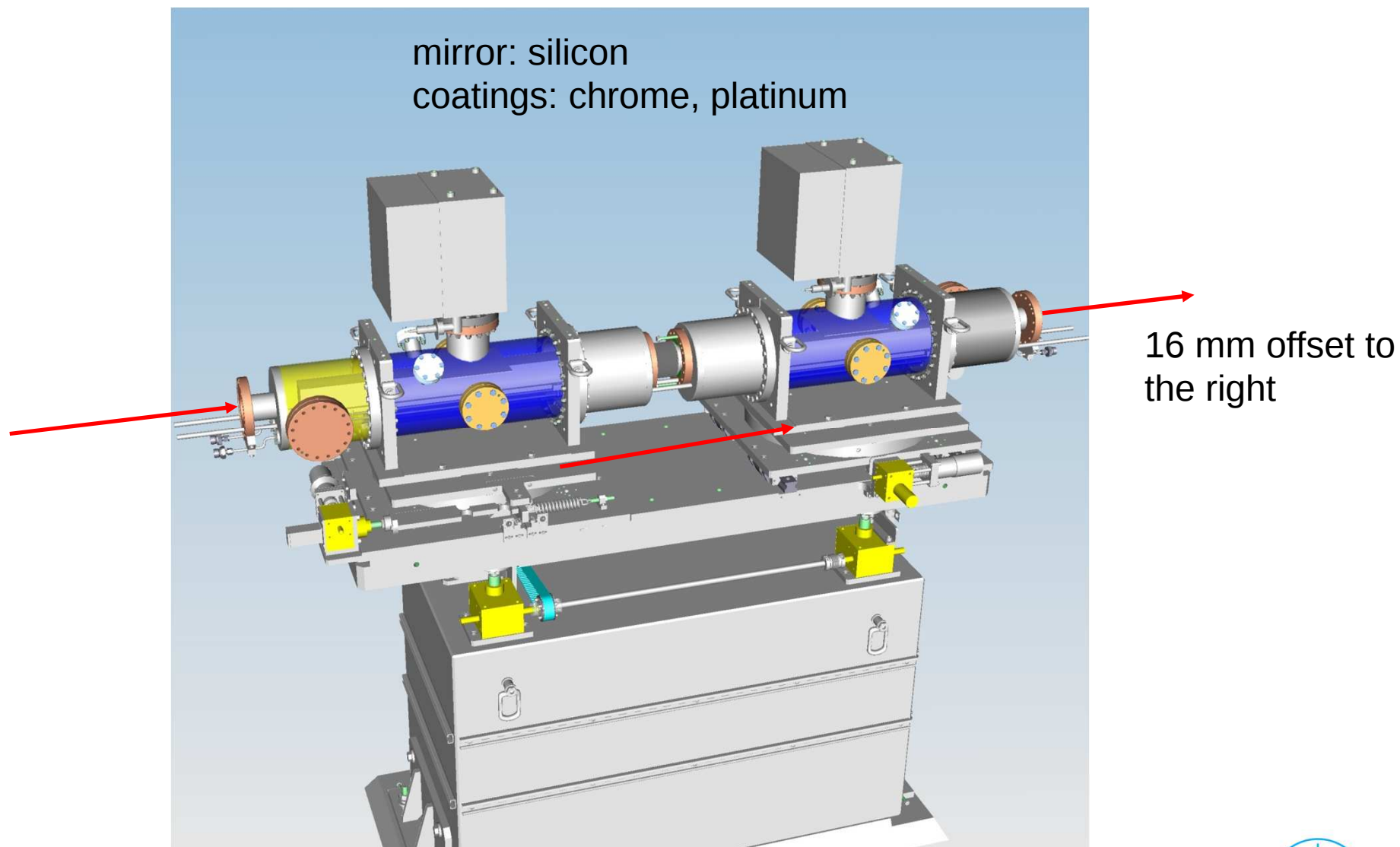
Mirror optics – P03 M1 + M2

Resolutions for all mirror optics:

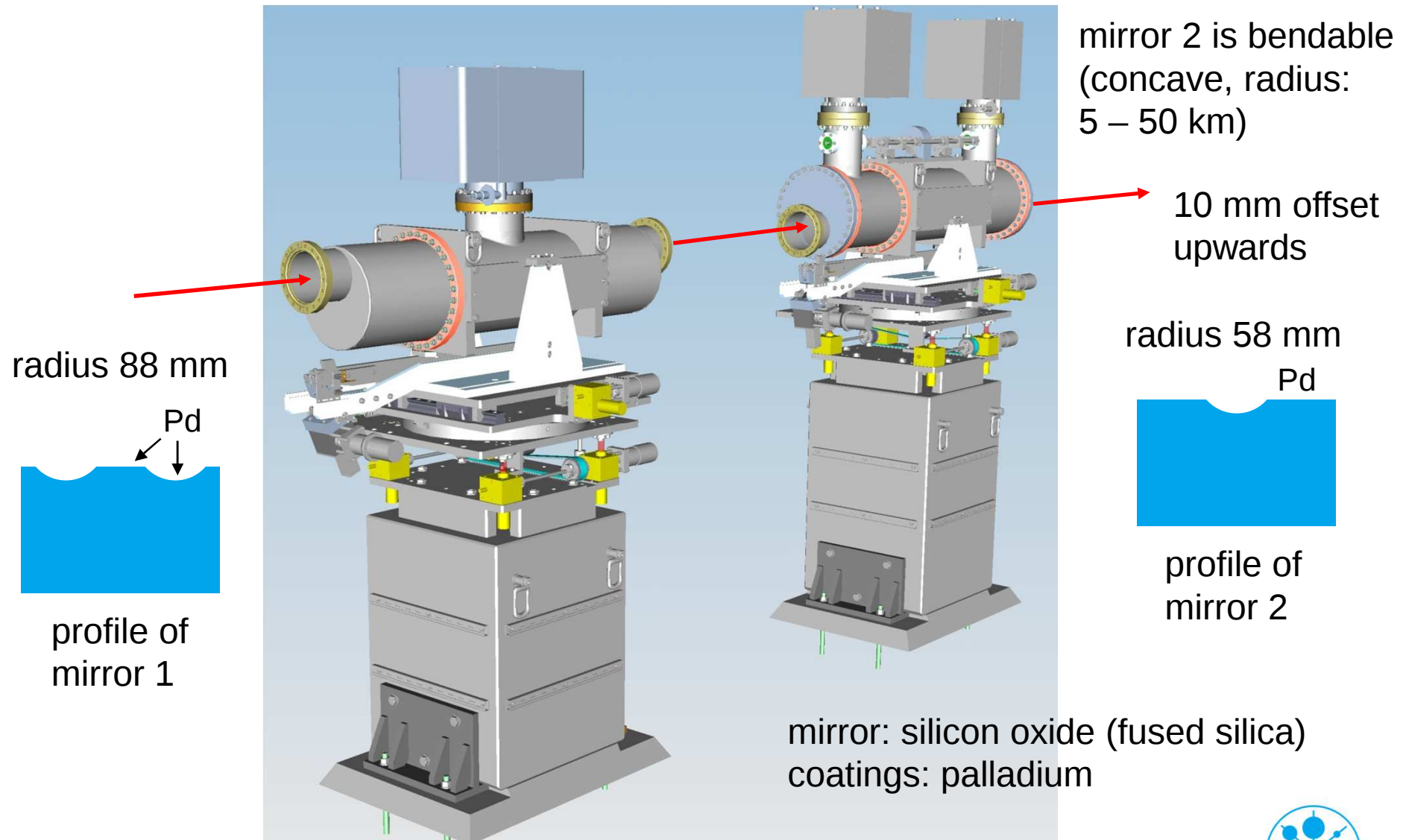
- translations: 100 nm
- rotary table: 40 nrad
- pitch angle: 15,3 nrad



Mirror optics – P06 M1 + M2



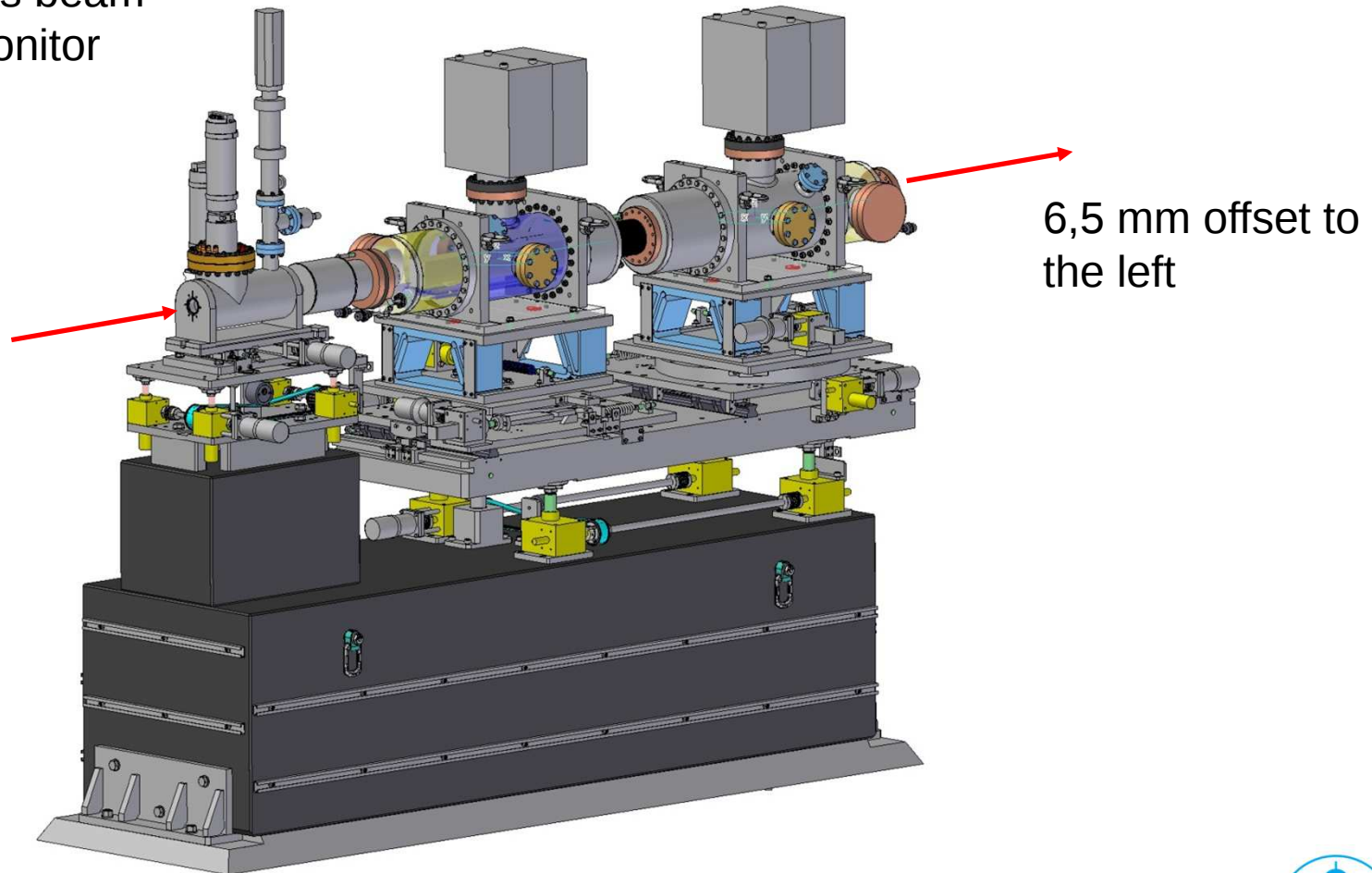
Mirror optics – P09 M1 + M2 (Resonant scattering/diffraction)



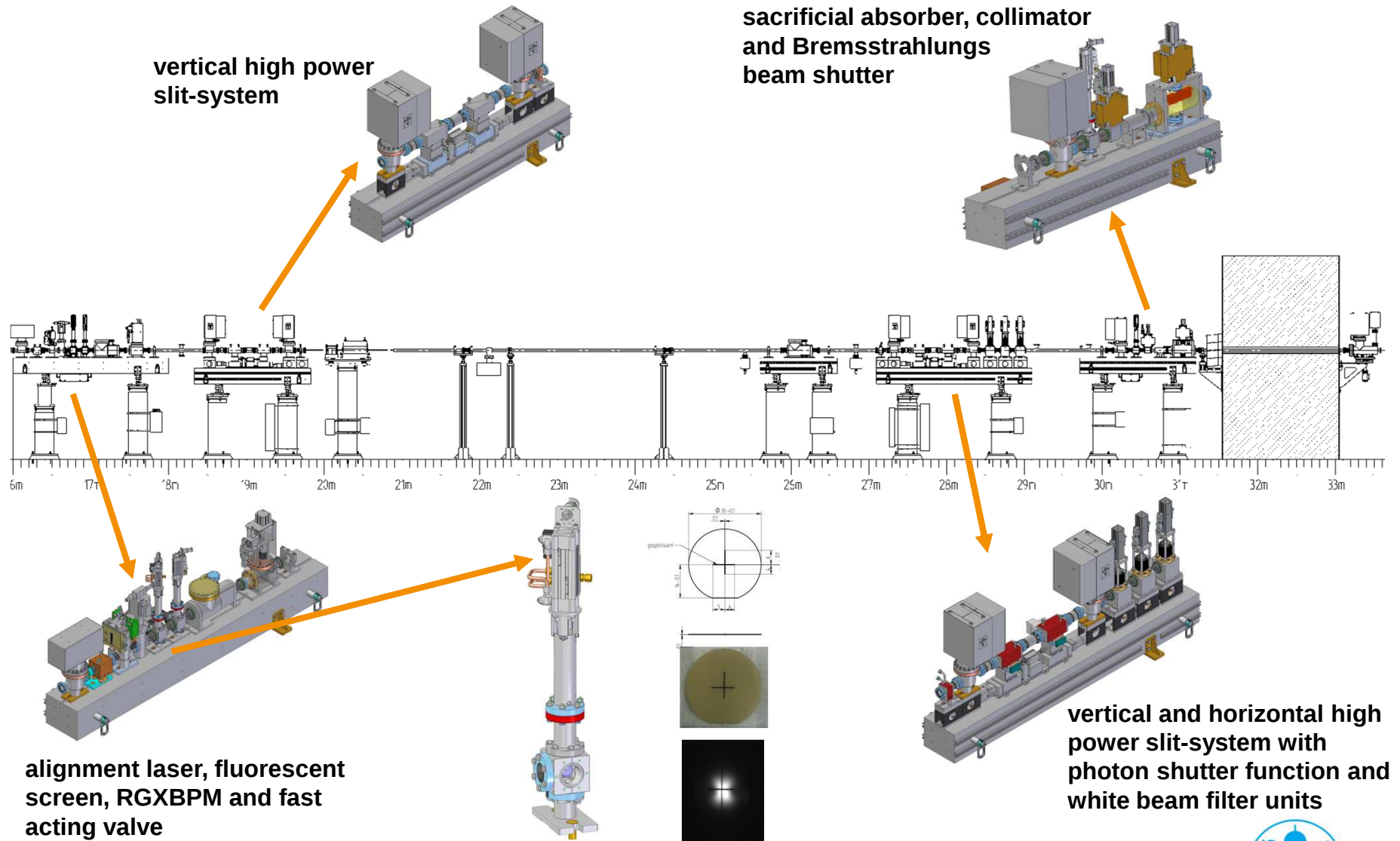
Mirror optics – P10 M1 + M2

mirror: silicon oxide (fused silica)
coatings: platinum, rhodium

residual gas beam
Position monitor



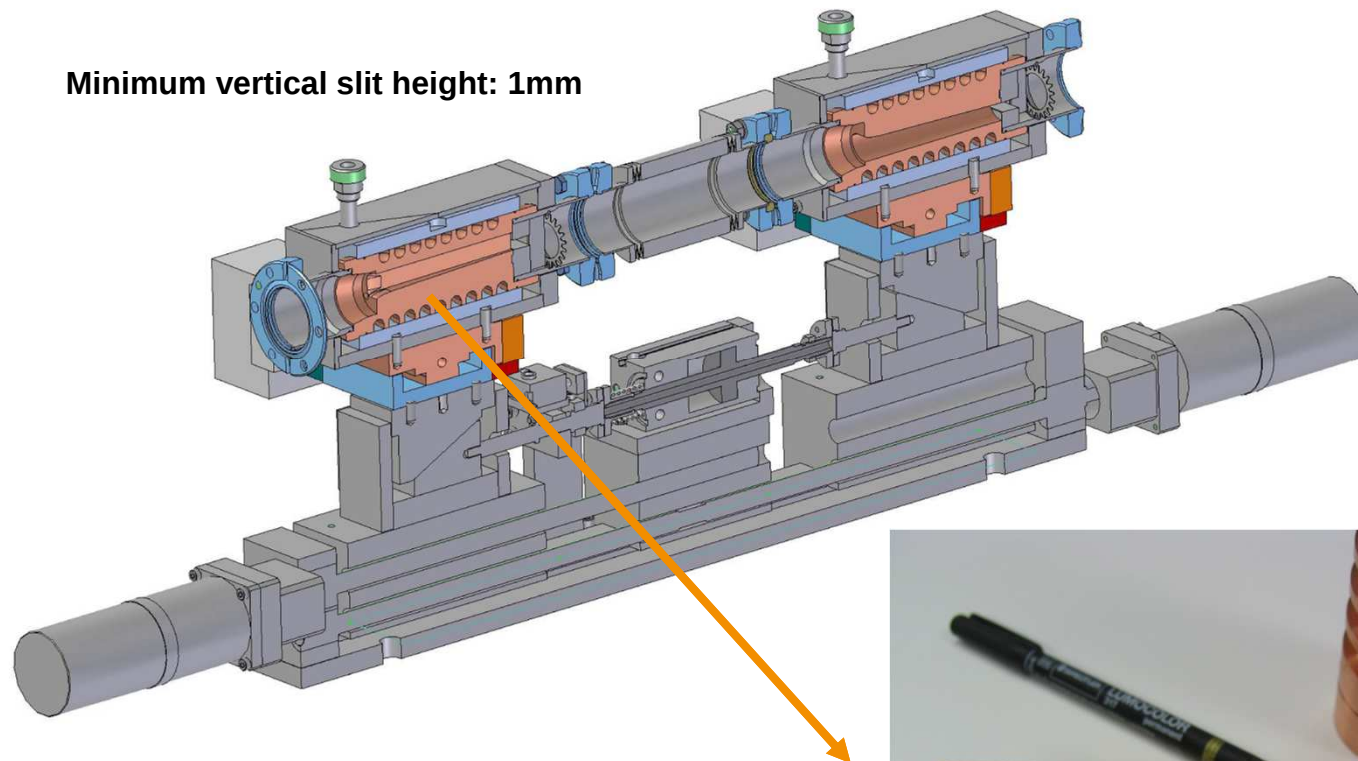
Petra III – Generic Frontend



diamond fluorescent screen

Petra III – Generic Frontend

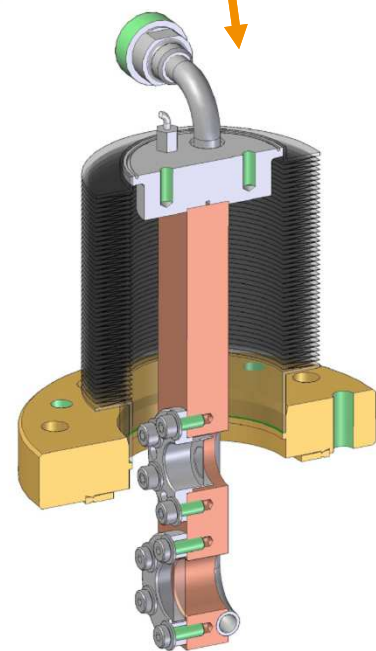
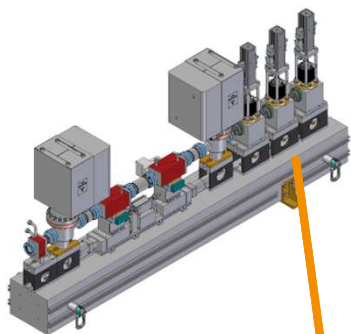
Minimum vertical slit height: 1mm



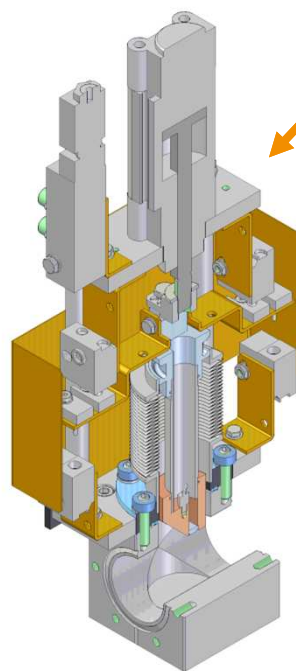
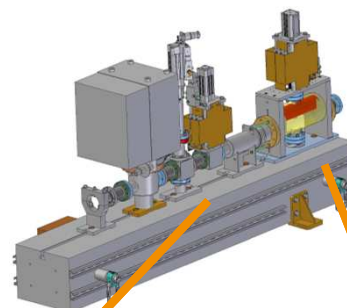
vertical high power
slit-system



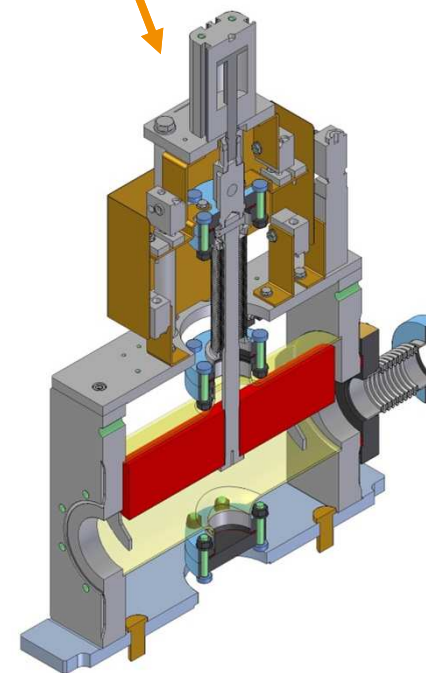
Petra III – Generic Frontend



water cooled filter unit
glassy carbon
CVD-diamond
copper



sacrificial absorber



Bremsstrahlungs beam shutter

Conclusion and Outlook

- Large offset monochromators reach their specifications
- Stable mirror systems in different configurations
- High heat load monos with channel cut option
- New generation of high heat load monos for Petra Extension in development
- Generic Frontend will be used for Petra Extension

